

DETAILED ACTION

Allowable Subject Matter

Claims 1-6 and 8-25 are allowed. The following is an examiner's statement of reasons for allowance:

Regarding claim 1, prior art fails to teach a method of making a transistor having first and second electrodes, a semiconductive layer, and a dielectric layer, said semiconductive layer comprising a semiconductive polymer and said dielectric layer comprising an insulating polymer; characterized in that said method comprises the steps of depositing on the first electrode a layer of a solution, said solution comprising material for forming the semiconductive layer and material for forming the dielectric layer; wherein said solution comprises a diblock polymer, said diblock polymer comprising a semiconductive block for forming the semiconductive layer and a dielectric block for forming the dielectric layer. Claims 2, 3, and 8-22 are dependent upon claim 1 and are therefore allowable.

Regarding claim 4, prior art fails to teach a method of making a transistor having first and second electrodes, a semiconductive layer, and a dielectric layer; said semiconductive layer comprising a semiconductive polymer and said dielectric layer comprising an insulating polymer; characterized in that said method comprises the

Art Unit: 2823

steps of (i) depositing on the first electrode a layer of a solution, said solution comprising material for forming the semiconductive layer and material for forming the dielectric layer, wherein the material for forming the dielectric layer is mixed with the material for forming the semiconductive layer in the solution. Claims 5, 6, and 23-25 are dependent upon claim 4 and are therefore allowable.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. US Patent Application Publication 2003/0178626, issued to Sugiyama et al, discloses forming a light emitting element that uses a diblock polymer. US Patent Application Publications 2004/0248338 and 2004/0253836, both issued to Sirringhaus, discloses method for alignment of a polymer layer.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to QUOVAUNDA JEFFERSON whose telephone number

Art Unit: 2823

is (571)272-5051. The examiner can normally be reached on Monday thru Friday 7AM-3:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew Smith can be reached on 571-272-1907. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Matthew S. Smith/
Supervisory Patent Examiner, Art
Unit 2823

QVJ